

IN THE CLAIMS:

Please cancel Claims 65 to 72 without prejudice to or disclaimer of the subject matter presented therein. Please amend Claim 60 as shown below.

1 to 59. (Cancelled)

60. (Currently Amended) A processing apparatus comprising:

a chamber accommodating a processing portion;

an exhaust gas line, connected to said chamber, for exhausting ambient gas in said chamber;

a vacuum pump, connected to said exhaust ~~has~~ gas line, for compressing the ambient gas;

a supply line for supplying the compressed ambient gas into said chamber;

a high pressure gas supply line branched out of said supply line; and

a compressor, provided in said high pressure gas supply line, for further compressing the ambient gas compressed by said vacuum pump.

61. (Previously Presented) The apparatus according to Claim 60, further comprising a stage provided in said chamber, and a hydrostatic bearing for movably guiding said stage, wherein said high pressure gas supply line supplies the ambient gas to said hydrostatic bearing.

62. (Previously Presented) The apparatus according to Claim 60, further comprising a pressure sensor for detecting a pressure in said chamber, and a controller for controlling a pressure in said chamber on the basis of an output of said pressure sensor.

63. (Previously Presented) An exposure apparatus comprising a processing apparatus as defined in Claim 60, a stage for positioning a substrate to be exposed in said processing apparatus, and a laser interferometer for detecting a position of said stage.

64. (Previously Presented) A device manufacturing method comprising a step of applying a photosensitive material on a substrate, and a step of exposing a substrate by the apparatus as defined in Claim 63, and a step of developing the substrate thus exposed.

65 to 72. (Cancelled)